

20th Anniversary of KSDT
KISM 2022
Korean International Semiconductor Conference on Manufacturing Technology 2022
November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[MC2] Etch Technology Trend
Session Date:	November 14 (Mon.), 2022
Session Time:	15:00-16:45
Session Room:	Room C (Grand Ballroom 2, 2F)
Session Chair:	Prof. Geun Young Yeom (Sungkyunkwan Univ., Korea)

[MC2-1] [Invited] 15:00-15:30

Atomic Layer Modification/Etching of 2-Dimensional MoS₂ Semiconductor Material

Ji Eun Kang and Geun Young Yeom (Sungkyunkwan Univ., Korea)

[MC2-2] [Invited] 15:30-16:00

The Story of Plasma Patterning

Kyoungho Jang, Chungil Hyun, Hyungi Kim, Sangwoo Lee, Youngseop Rah, Changgu Jung, Changwon Choi, Seongtae Oh, Youngwoo Park, and Jaihyung Won (Tokyo Electron Korea Ltd., Korea)

[MC2-3] [Plenary] 16:00-16:45

Dry Etch Technologies for Next Generation Small Pitch Patterning at EUV Lithography Era

Jong Chul Park (Samsung Electronics Co., Ltd., Korea)